

ABSTRACT OF THE DISCLOSURE

A film-formation apparatus includes a film-formation chamber and a source gas supplying apparatus supplying a source gas to the film-formation chamber together with a carrier gas, wherein the source gas supplying apparatus includes a concentration detector detecting a concentration of the source gas and a gas flow controller controlling a flow rate of an inert gas added to the carrier gas based on a result of measurement of the concentration of the source gas obtained by the concentration detector.